

ABSTRACT

A process chamber **35** capable of processing a substrate **30** and monitoring a process conducted on the substrate **30**, comprises a support **45**, a gas inlet, a gas energizer, an exhaust **85**, and a wall **38** having a recess **145** that is sized to reduce the deposition of process residues therein. A process monitoring system **35** may be used to monitoring a process that may be conducted on a substrate **30** in the process chamber **25** through the recess **145** in the wall **38**.

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